

IN THE CLAIMS

Please cancel claims 10, 12, 13, 28, and 29, and amend claim 15 as shown below in the listing of claims.

Claims 1-10 (canceled)

Claim 11 (previously presented): A liquid processing apparatus comprising:

a processing container surrounding a processing chamber in which a plurality of substrates to be processed are accommodated, the substrates being shaped in circular plates;

a substrate holder arranged in the processing container for holding the substrates which are juxtaposed in an axial direction of the circular substrates in such a way that processing surfaces of the substrates are arranged in parallel with each other and for rotating the substrates about the axis of the circular substrates; and

a nozzle arranged in the processing container for supplying the substrates with a processing liquid thereby to carry out a liquid process, the nozzle having ejecting orifices to eject the processing liquid in a plane which is substantially parallel with the substrates, the ejecting orifices being formed so as to eject the processing liquid towards substantial centers of the substrates held by the substrate holder and obliquely to the processing surfaces of the plural substrates in such a way that the plane of ejecting processing liquid and the surface of the substrates forms a little angle,

wherein the nozzle comprises:

a nozzle body provided with a plurality of pedestals formed corresponding to the substrates to be processed; and

nozzle members attached to the plurality of pedestals, the nozzle members having the ejecting orifices formed therein; and

wherein surfaces of the pedestals incline so that the nozzle members can eject the processing liquid obliquely to the processing surfaces of the substrates held by the substrate holder, in such a way that the plane of ejecting processing liquid and the surface of the substrates forms a little angle.

Claims 12-13 (canceled)

Claim 14 (previously presented): A liquid processing apparatus as claimed in Claim 11, wherein the nozzle comprises:

- a first nozzle, and
- a second nozzle,

wherein the first nozzle and the second nozzle are separated from each other in the circumferential direction of the substrates, the first nozzle having a plurality of first ejecting orifices to eject the processing liquid to alternately-positioned ones of the plural substrates to be processed, and the second nozzle having a plurality of second ejecting orifices to eject the processing liquid to alternately-positioned ones of the plural substrates except the alternately-positioned substrates charged by the first nozzle.

Claim 15 (currently amended): A liquid processing apparatus as claimed in Claim ~~10 or~~ 11,

wherein the ejecting orifices are arranged in a space above a horizontal plane including central axes of the substrates to be processed.

Claim 16-17 (canceled)

Claim 18 (previously presented): A liquid processing apparatus for processing wafers comprising:

wafer holding members for holding a plurality of wafers juxtaposed in an axial direction of the wafers, the axial direction of the wafers being a horizontal direction, the wafer holding members extending in the axial direction along circumferences of the plurality of wafers;

a pair of circular plates arranged at both ends of the wafer holding members for supporting the wafer holding members and rotating the wafers about a rotating shaft;

a processing container for accommodating the circular plates and the wafer holding members therein, the processing container formed in a cylindrical shape and having a circumferential inner surface facing the peripheral parts of the wafers and a side inner surface facing the pair of circular plates;

a nozzle arranged on the circumferential inner surface of the processing container for supplying the wafers with a processing liquid from a source thereof to carry out a process for processing wafers; and

ejecting orifices formed on the side inner surface of the processing container, the ejecting orifices being formed so that the ejecting orifices eject a cleaning liquid from a source thereof towards a surface of the circular plates facing the side inner surface of the processing container so as to clean the surface of the circular plates.

Claims 19-23 (canceled)

Claim 24 (previously presented): A liquid processing apparatus comprising:

a processing container surrounding a processing chamber in which a plurality of substrates to be processed are accommodated, the substrates being shaped in circular plates;

a substrate holder arranged in the processing container for holding the substrates which are juxtaposed in an axial direction of the circular substrates in such a way that processing surfaces of the substrates are arranged in parallel with each other and for rotating the substrates about the axis of the circular substrates, the axis direction of the substrates being a horizontal direction; and

a nozzle arranged in the processing container for supplying the substrates with a processing liquid thereby to carry out a liquid process, the nozzle having ejecting orifices ejecting the processing liquid towards substantial centers of the substrates held by the substrate holder and obliquely to the processing surfaces of the plural substrates in such a way that the plane of ejecting processing liquid and the surface of the substrates forms a little angle;

wherein the ejecting orifices are located so that the processing liquid is ejected against each processing surface of the rotating substrates held by the substrate holder in such a way that a width of the plane-ejected processing liquid is generally equal to a radius of the circular substrate, on the processing surface, and

wherein the ejecting orifices are arranged in a space above a horizontal plane including central axes of the substrates to be processed, and also arranged in respective positions excluding an upper-projected space of the substrates.

Claim 25 (previously presented): A liquid processing apparatus according to claim 24,

wherein the substrate holder rotates so that a direction of ejected liquid is opposite to a moving direction of a peripheral part of the rotating circular substrate in an area where

processing liquid comes into contact with the surface of the rotating circular substrate held by the substrate holder.

Claim 26 (canceled)

Claim 27 (previously presented) A liquid processing apparatus comprising:

a processing container surrounding a processing chamber in which a plurality of substrates to be processed are accommodated, the substrates being shaped in circular plates;

a substrate holder arranged in the processing container for holding the substrates which are juxtaposed in an axial direction of the circular substrates in such a way that processing surfaces of the substrates are arranged in parallel with each other and for rotating the substrates about the horizontal axis of the circular substrates, the axis direction of the substrates being a horizontal direction; and

a nozzle arranged in the processing container for supplying the substrates with a processing liquid thereby to carry out a liquid process, the nozzle having a plurality of ejecting orifices juxtaposed with the plural substrates, the ejecting orifices ejecting the processing liquid in a plane which is substantially parallel with the substrates held by the substrate holder;

wherein the ejecting orifices are formed so as to eject the processing liquid toward substantial centers of the substrates held by the substrate holder and obliquely to the processing surfaces of the plural substrates in such a way that the plane of ejecting processing liquid and the surface of the substrates forms a little angle, the ejecting orifices being formed so as to eject the processing liquid against the processing surfaces of the substrates held by the substrate holder so that a width of the plane-ejected processing liquid is generally equal to the diameters of the substrates, and

wherein the nozzle comprises:

a first nozzle, and

a second nozzle,

wherein the first nozzle and the second nozzle are separated from each other in the circumferential direction of the substrates, the first nozzle having a plurality of first ejecting orifices to eject the processing liquid to alternately-positioned ones of the plural substrates to be processed, and the second nozzle having a plurality of second ejecting orifices to eject the processing liquid to alternately-positioned ones of the plural substrates except the alternately-positioned substrates charged by the first nozzle.

Claim 28-29 (canceled)